

EL844046498

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

PRIORITY Application Serial No. .... 09/507,193  
PRIORITY Filing Date ..... February 18, 2000  
Inventor ..... Mark Fischer et al.  
Assignee ..... Micron Technology, Inc.  
PRIORITY Group Art Unit ..... 1765  
PRIORITY Examiner ..... D. Deo  
Attorney's Docket No. .... MI22-1777  
Title: Semiconductor Processing Methods of Forming a Conductive  
Projection and Methods of Increasing Alignment Tolerances

**Preliminary Amendment to Accompany the filing of a Continuation  
Application Under 37 C.F.R. 1.53(b)**

To: Patent Application  
Assistant Commissioner for Patents  
Washington, D.C. 20231

From: Bernard Berman (Tel. 509-624-4276; Fax 509-838-3424)  
Wells, St. John, Roberts, Gregory & Matkin P.S.  
601 W. First Avenue, Suite 1300  
Spokane, WA 99201-3828

Sir:

This is a preliminary amendment accompanying a Request for Continuation Application for the above-entitled patent application. Prior to examining the application, please enter the amendments and consider the remarks contained herein.